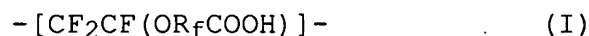


What is claimed is:

1. An anti-reflective coating composition of 7 or less in pH which comprises a fluorine-containing polymer, an acid, an amine and an aqueous solvent capable of dissolving these components.

2. The anti-reflective coating composition as described in claim 1, wherein the fluorine-containing polymer is a fluorine-containing polymer containing a polymer unit represented by the following general formula (I) or a fluorine-containing polymer containing both a polymer unit represented by the following general formula (I) and a polymer unit represented by the following general formula (II):



wherein R_f represents a straight or branched perfluoroalkyl group which may contain an etheric oxygen atom;



wherein X represents a fluorine atom or a chlorine atom.

3. The anti-reflective coating composition as described in claim 1, wherein the acid is at least one member selected from the group consisting of sulfuric acid, hydrochloric acid, nitric acid, phosphoric acid, hydrofluoric acid, hydrobromic acid, alkylsulfonic acid, alkylbenzenesulfonic acid, alkylcarboxylic acid, alkylbenzenecarboxylic acid, and those obtained by replacing all or part of the hydrogen atoms of the aforesaid alkyl group by fluorine atoms.

4. The anti-reflective coating composition as described in claim 1, wherein the amine is at least one member selected from the group consisting of NH_3 , $\text{N(CH}_3)_4\text{OH}$, alkanolamine, alkylamine

and aromatic amine.

5. The anti-reflective coating composition as described in claim 1, wherein the aqueous solvent is water.

6. A pattern-forming method which includes a step of applying the anti-reflective coating compositions described in one of claims 1 to 5 on a photoresist film and, if necessary, a heating step.